

# of Book: Handbook of Thin Film Process Technology

External Publication Status: published

Copyright: © 1998 - 2003 IOP Publishing

Audience: Experts Only

Title of Book: Handbook of Thin Film Process Technology

Date of Publication (YYYY-MM-DD): 2001

Abstract / Description: The Handbook of Thin Film Process Technology is a practical handbook for the thin film scientist, engineer and technician. The main work is regularly updated with new material, and this volume is a special issue on substrate cleaning which will be of interest to industrial and academic researchers in the semiconductor and optics industry in addition to owners of the main Handbook. This supplement includes recipes which give precise instructions for the cleaning of specific substrates, for specific film depositions, or using specific techniques. In addition, general articles evaluate the cleaning procedure, covering the usual contaminants, handling and storage of substrates, chemicals (for instance the importance of the pH of solution, particle deposition), DI quality (level of contamination, water drops), what is removed, drying (e.g. the Marangoni effect), and the surface of the substrate before deposition (composition, morphology, hydrophilic, hydrophobic). Keywords: G1 Cleaning of silicon for ULSI and CVD (Huang); G2 Chemical composition and morphology of silicon surfaces (K Jacobi); G3 Surface analyses of substrates for microelectronic device fabrication (Berbezier); plus nine recipes for film deposition for electronic applications: Wet chemical cleaning of Si for IC manufacturing (Christernson and Butterbaugh); Cleaning of SiC and Al<sub>2</sub>O<sub>3</sub> substrates for MBE and MOCVD deposition of AlN, GaN and InAlGaN (Kouvetakis); Cleaning of II-VI substrates for MBE and MOCVD deposition (N Magnea); Dry cleaning of silicon (plasma, UV-ozone, atomic H) (I Eisele); Vapor phase cleaning (Butterbaugh); Wet chemical etching of GaS and InP for MOCVD deposition of III-V (Mason); Wet chemical etching of Si for MBE and GSMBE of Si and SiGeC (ex-situ and in-situ) (Le Thanh); Wet chemical etching of Si for CVD of Si and SiGeC (Tillack).

Place of Publication: Bristol, UK

Full Name of Book-Editor(s): Glocker, David A.; Shah, S. Ismat

Communicated by: Gerhard Ertl

Affiliations:

Fritz-Haber-Institut/Physical Chemistry

Identifiers:

ISBN:978-0750303118;ISBN:0750303115

Thin film process technology. Publication, Distribution, etc.: Bristol, UK ; Philadelphia . On this site it is impossible to download the book, read the book online or get the contents of a book. Site Directory is updated by users of the public Internet sources and in no way affects the rights of copyright holders. The administration of the site is not responsible for the content of the site. The data of catalog based on open source database. All rights are reserved by their owners. [pdf, txt, ebook] Download book Handbook of thin film process technology / editors, David A. Glocker, S. Ismat Shah. online for free. Glang, Handbook of Thin Film Technology, Mc Graw Hill Book.

Citation: Journal of Vacuum Science & Technology B 32, 051808 (2014), doi: by the AVS: Science & Technology of Materials, Interfaces, and Processing. In (5) D.S. Campbell, Handbook of Thin Films Technology, McGraw. Handbook of Thin Film Materials: Deposition and processing of thin films Fundamentals of Semiconductor Processing Technology , Badih El-Kareh, Dec

31, 1994. wordpress.com/2014/08/english-on-the-job-metal-product-assembler.pdf. 1.1.1 Demand for electrodes in ceramic thin and thick films device D. A. Glocker, Handbook of Thin Film Process Technology , Institute of Physics. Publishing. mechanical strength, electrocatalyst and manufacturing technology. - Elsevier, 2012. - 397 p. - The Handbook of Thin Film Deposition is a comprehensive reference focusing on thin film technologies and applications used in the semiconductor industry and the closely related areas of thin film deposition, thin film micro properties, photovoltaic solar... Woodhead Publishing, 2011, 4162 pages Thin-film technology is used in many applications such as microelectronics, optics, magnetics, hard and corrosion resistant coatings and micromechanics. This book provides a review of the theory and techniques for the deposition of thin films. It will help the reader understand the variables affecting growth kinetics and microstructural 31,68 MB.

